



# X-Ray Scattering of Indium Oxide Thin Films



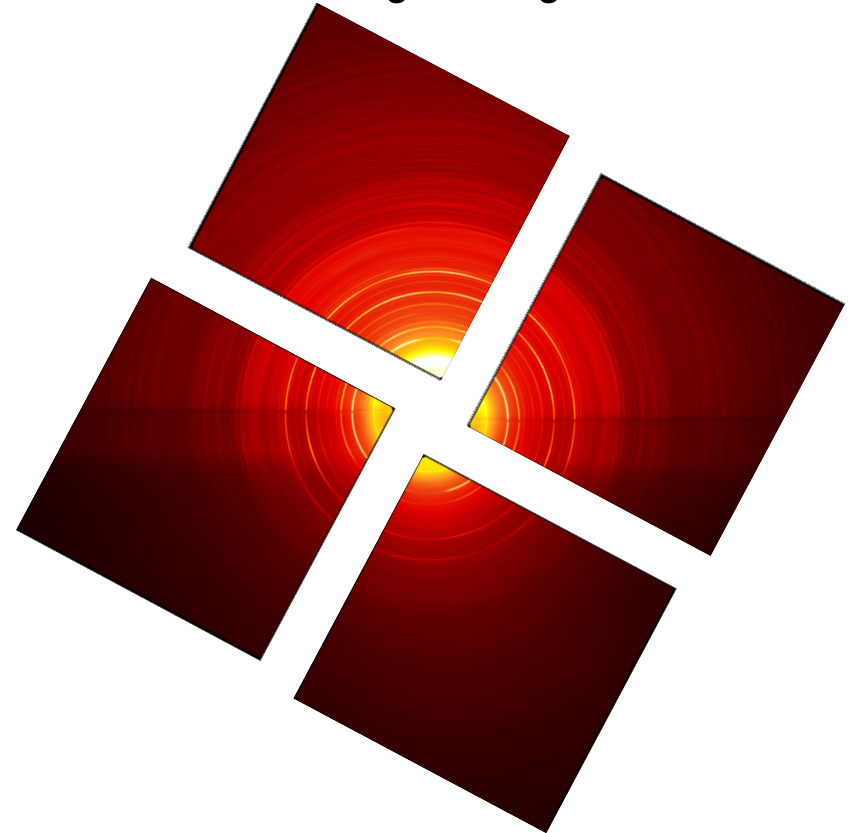
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Indium oxide has important applications in optoelectronics and photovoltaics devices due to its transparency in the visible region and semiconducting properties. The fraction of amorphous to crystalline material dramatically affects the electrical performance of these type of samples. X-ray diffraction experiments were performed on thin films exhibiting a wide range of crystallinity in order to investigate changes in the local structure and their effect on electrical properties.



Two-dimensional image of x-ray diffraction rings of a partially crystalline indium oxide film